

and which contains the substrate processing apparatus therein;

an environment sensor provided in at least one of the first and the second chambers which measures an environment in said at least one of the first and the second chambers; and

Cond  
cl a control device electrically connected to the environment sensor, said control device controlling the environment in said at least the other of the first and the second chambers on the basis of a measured value given from said environment sensor in such a manner that the environment of said exposure apparatus becomes the same as the environment of said substrate processing apparatus.

---

5. (Twice Amended) A lithography method for controlling an environment in an exposure apparatus which exposes a substrate and which is provided adjacent to a substrate processing apparatus which processes the substrate before or after exposure, the method comprising the steps of:

obtaining data regarding the environment in a processing chamber in which said substrate processing apparatus is provided; and

controlling the environment in an exposure chamber in which said exposure apparatus is provided and which is provided separately from the processing chamber, on the basis of the obtained data.

---

12. (Twice Amended) A lithography method for controlling an environment in a substrate processing apparatus which processes a substrate before or after exposure, said substrate processing apparatus being provided adjacent to an exposure apparatus which exposes the substrate before or

after the processing, the method comprising the steps of:

obtaining data regarding the environment in an exposure chamber in which said exposure apparatus is provided; and

controlling the environment in a processing chamber in which said processing apparatus is provided and which is provided separately from the exposure chamber, on the basis of the obtained data.

---

C4 20. (Twice Amended) A method for making an exposure apparatus which exposes a substrate, said exposure apparatus being provided adjacent to a substrate processing apparatus contained in a processing chamber which processes the substrate before or after exposure of the substrate, the method comprising the steps of:

providing an exposure body in an exposure chamber different from the processing chamber, the exposure body performing an exposure operation of the substrate;

providing an adjusting device which adjusts an environment in said exposure chamber; and

providing a control device which controls said adjusting device on the basis of data regarding the environment in said processing chamber.

---

C5 23. (Twice Amended) A method for making a substrate processing apparatus which processes a substrate and which is provided adjacent to an exposure apparatus contained in an exposure chamber which exposes the substrate before or after the processing of the substrate, the method comprising the steps of:

providing an exposure body in a processing chamber different from the exposure chamber,  
the processing body performing a processing operation to the substrate;

providing an adjusting device which adjusts an environment in said processing chamber; and

providing a control device which controls said adjusting device on the basis of data regarding  
the environment in said exposure chamber.

---

26. (Twice Amended) A lithography method using an exposure apparatus which exposes a  
substrate and a substrate processing apparatus which processes the substrate before or after exposure,  
the method comprising the steps of:

obtaining data regarding an environment within a chamber of one of an exposure chamber  
in which said exposure apparatus is contained and a processing chamber in which said substrate  
processing apparatus is contained and which is provided separately from the exposure chamber; and

controlling the environment in the other chamber of the exposure chamber and the processing  
chamber on the basis of the obtained data.

27. (Twice Amended) An exposure apparatus which exposes a substrate and which is  
provided adjacent to a substrate processing apparatus contained in a processing chamber which  
processes the substrate before or after exposure of the substrate, the exposure apparatus comprising:

an exposure chamber which is separate from the processing chamber and contains the  
exposure apparatus;

an adjusting device connected to said exposure chamber and which adjusts an environment

in said exposure chamber; and

a control device electrically connected to said adjusting device and which controls said adjusting device on the basis of data regarding the environment in said processing chamber.

28. (Twice Amended) A substrate processing apparatus which processes a substrate and which is provided adjacent to an exposure apparatus contained in an exposure chamber which exposes the substrate before or after the substrate processing, the substrate processing apparatus comprising:

a processing chamber which is separate from the exposure chamber and contains the substrate processing apparatus;

an adjusting device connected to said processing chamber and which adjusts an environment in said processing chamber; and

a control device electrically connected to said adjusting device and which controls said adjusting device on the basis of data regarding environment in said exposure chamber.

---

Cond  
C6